

# DIANHYDRIDES & IMIDES 1040A

### **DESCRIPTION**

Transparent, high flow polyetherimide.

## TYPICAL PROPERTY VALUES

Revision 20231109

PROPERTIES	TYPICAL VALUES	UNITS	TEST METHODS
MECHANICAL			
Tensile Stress, yld, Type I, 5 mm/min	97	MPa	ASTM D638
Tensile Strain, brk, Type I, 5 mm/min	10	%	ASTM D638
Tensile Modulus, 5 mm/min	3440	MPa	ASTM D638
Flexural Stress, yld, 2.6 mm/min, 100 mm span	159	MPa	ASTM D790
Flexural Modulus, 2.6 mm/min, 100 mm span	3510	MPa	ASTM D790
IMPACT			
Izod Impact, unnotched, 23°C	470	J/m	ASTM D4812
Izod Impact, notched, 23°C	21	J/m	ASTM D256
Gardner, 23°C	8	J	ASTM D3029
THERMAL			
HDT, 1.82 MPa, 6.4 mm, unannealed	196	°C	ASTM D648
PHYSICAL			
Specific Gravity	1.27	-	ASTM D792
Mold Shrinkage, flow, 3.2 mm	0.5 – 0.7	%	SABIC method
Melt Flow Rate, 295°C/6.6 kgf	6.6	g/10 min	ASTM D1238

### **ADDITIONAL PRODUCT NOTES**

No PFAS intentionally added: The grade listed in this document does not contain PFAS intentionally added during Seller's manufacturing process and is not expected to contain unintentional PFAS impurities. Each user is responsible for evaluating the presence of unintentional PFAS impurities.

## **DISCLAIMER**

Any sale by SABIC, its subsidiaries and affiliates (each a "seller"), is made exclusively under seller's standard conditions of sale (available upon request) unless agreed otherwise in writing and signed on behalf of the seller. While the information contained herein is given in good faith, SELLER MAKES NO WARRANTY, EXPRESS OR IMPLIED, INCLUDING MERCHANTABILITY AND NONINFRINGEMENT OF INTELLECTUAL PROPERTY, NOR ASSUMES ANY LIABILITY, DIRECT OR INDIRECT, WITH RESPECT TO THE PERFORMANCE, SUITABILITY OR FITNESS FOR INTENDED USE OR PURPOSE OF THESE PRODUCTS IN ANY APPLICATION. Each customer must determine the suitability of seller materials for the customer's particular use through appropriate testing and analysis. No statement by seller concerning a possible use of any product, service or design is intended, or should be construed, to grant any license under any patent or other intellectual property right.